

## Inventor Name Search Result

Your Search was:

Last Name = DOPPER

First Name = GEBHARD

Application#	Patent#	Status	Date Filed	Title	Inventor Name 4
<a href="#">10085527</a>	Not Issued	071	02/28/2002	METHOD AND DEVICE FOR TREATING THE SURFACE OF A PART	DOPPER, GEBHARD
<a href="#">10045770</a>	<a href="#">6602542</a>	150	01/10/2002	DEVICE FOR CLEANING AN ARTICLE	DOPPER, GEBHARD
<a href="#">09840556</a>	<a href="#">6382920</a>	150	04/23/2001	ARTICLE WITH THERMAL BARRIER COATING AND METHOD OF PRODUCING A THERMAL BARRIER COATING	DOPPER, GEBHARD
<a href="#">09840552</a>	Not Issued	071	04/23/2001	PROCESS FOR CLEANING AN ARTICLE, PROCESS FOR COATING AN ARTICLE, AND DEVICE THEREFOR	DOPPER, GEBHARD

Inventor Search Completed: No Records to Display.

**Search Another: Inventor**

<b>Last Name</b>	<b>First Name</b>	<b>Search</b>
DOPPER	GEBHARD	

To go back use Back button on your browser toolbar.

Back to [PALM](#) | [ASSIGNMENT](#) | [OASIS](#) | [Home page](#)

L Number	Hits	Search Text	DB	Time stamp
1	1	6602542.pn.or6382920.pn.	USPAT; US-PGPUB	2003/11/21 08:55
2	2	6602542.pn. or 6382920.pn.	USPAT; US-PGPUB	2003/11/21 08:57
3	0	427/532,533,534,535	USPAT; US-PGPUB	2003/11/21 08:58
4	1077	(427/532,533,534,535).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
5	280	(427/551).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
6	746	(427/596,597).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
7	919	(427/255.11,255.19,255.21,255.5).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
8	734	(427/318,319).CCLS.	USPAT; US-PGPUB	2003/11/21 08:58
9	2014	(216/63,64,67,74,75).CCLS.	USPAT; US-PGPUB	2003/11/21 08:59
10	1291	(204/192.32,192.35,298.31,298.34).CCLS.	USPAT; US-PGPUB	2003/11/21 08:59
11	6535	((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)	USPAT; US-PGPUB	2003/11/21 08:59
12	3	(clean\$3 near5 (plasma or (glow adj discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) and (Dopper.in. or Siemens.as.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:02
13	9	(clean\$3 near5 (plasma or (glow adj discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:11
14	7	((clean\$3 near5 (plasma or (glow adj discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))) not ((clean\$3 near5 (plasma or (glow adj discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) and (Dopper.in. or Siemens.as.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:02
15	2	((((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))) and ((electron near3 heat\$3) same ((plasma or ion or sputter\$3 or (glow adj discharge)) near3 clean\$3))	USPAT; US-PGPUB	2003/11/21 09:05
16	49	((electron near5 heat\$3) same ((plasma or ion or sputter\$3 or (glow adj discharge)) near5 clean\$3))	USPAT; US-PGPUB	2003/11/21 09:09

17	47	((electron near5 heat\$3) same ((plasma or ion or sputter\$3 or (glow adj discharge)) near5 clean\$3))) not (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)) and ((electron near3 heat\$3) same ((plasma or ion or sputter\$3 or (glow adj discharge)) near3 clean\$3)))	USPAT; US-PGPUB	2003/11/21 09:05
18	21	((electron near5 heat\$3) same ((plasma or ion or sputter\$3 or (glow adj discharge)) near5 clean\$3)))	EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:09
19	100	(clean\$3 near5 (plasma or (glow adj discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:26
20	91	((clean\$3 near5 (plasma or (glow adj discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) ) not ((clean\$3 near5 (plasma or (glow adj discharge) or sputter\$3 or ion)) and (electron with (flow\$3 or flux\$3) with (control\$5 or switch\$3)) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:15
21	137	((((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.)) and (((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)) (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)) and ((alternat\$4 or switch\$3) with ((electron near2 (heat\$3 or bombard\$5)) or (positiv\$3 near2 bias)) with (((sputter\$3 or plasma or (glow adj discharge) or ion) near2 (clean\$3 or bombard\$5)) or (negativ\$4 near2 bias)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:16
22	6	((((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.)) and ((alternat\$4 or switch\$3) with ((electron near2 (heat\$3 or bombard\$5)) or (positiv\$3 near2 bias)) with (((sputter\$3 or plasma or (glow adj discharge) or ion) near2 (clean\$3 or bombard\$5)) or (negativ\$4 near2 bias)))	USPAT; US-PGPUB	2003/11/21 09:20
23	259	((alternat\$4 or switch\$3) with ((electron near2 (heat\$3 or bombard\$5)) or (positiv\$3 near2 bias)) with (((sputter\$3 or plasma or (glow adj discharge) or ion) near2 (clean\$3 or bombard\$5)) or (negativ\$4 near2 bias)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:21
24	59	((((alternat\$4 or switch\$3) with ((electron near2 (heat\$3 or bombard\$5)) or (positiv\$3 near2 bias)) with (((sputter\$3 or plasma or (glow adj discharge) or ion) near2 (clean\$3 or bombard\$5)) or (negativ\$4 near2 bias)))) and ((coat\$3 or \$4CVD or deposit\$3) near5 (substrate or base or metal\$4 or turbine or structure or body or basebody))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:28
25	207	(electron with (flow\$3 or flux\$3 or outflow\$3 or outflux\$3) with (control\$5) with (switch\$3 or alternat\$5 or (open\$3 near3 clos\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:27

26	223	(electron with (flow\$3 or flux\$3 or outflow\$3 or outflux\$3) with (control\$5 or regulat\$3 or adjust\$3) with (switch\$3 or alternat\$5 or (open\$3 near3 clos\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:28
27	3	( (electron with (flow\$3 or flux\$3 or outflow\$3 or outflux\$3) with (control\$5 or regulat\$3 or adjust\$3) with (switch\$3 or alternat\$5 or (open\$3 near3 clos\$3))) ) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:28
28	71	( (electron with (flow\$3 or flux\$3 or outflow\$3 or outflux\$3) with (control\$5 or regulat\$3 or adjust\$3) with (switch\$3 or alternat\$5 or (open\$3 near3 clos\$3))) ) and ((coat\$3 or \$4CVD or deposit\$3) near5 (substrate or base or metal\$4 or turbine or structure or body or basebody))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:28
29	65	(( (electron with (flow\$3 or flux\$3 or outflow\$3 or outflux\$3) with (control\$5 or regulat\$3 or adjust\$3) with (switch\$3 or alternat\$5 or (open\$3 near3 clos\$3))) ) and ((coat\$3 or \$4CVD or deposit\$3) near5 (substrate or base or metal\$4 or turbine or structure or body or basebody))) not ((( (electron with (flow\$3 or flux\$3 or outflow\$3 or outflux\$3) with (control\$5 or regulat\$3 or adjust\$3) with (switch\$3 or alternat\$5 or (open\$3 near3 clos\$3))) ) and (((427/532,533,534,535).CCLS.) ((427/551).CCLS.) ((427/596,597).CCLS.) ((427/255.11,255.19,255.21,255.5).CCLS.) ((427/318,319).CCLS.) ((216/63,64,67,74,75).CCLS.) ((204/192.32,192.35,298.31,298.34).CCLS.))) or (((alternat\$4 or switch\$3) with ((electron near2 (heat\$3 or bombard\$5)) or (positiv\$3 near2 bias)) with (((sputter\$3 or plasma or (glow adj discharge) or ion) near2 (clean\$3 or bombard\$5)) or (negativ\$4 near2 bias)))) and ((coat\$3 or \$4CVD or deposit\$3) near5 (substrate or base or metal\$4 or turbine or structure or body or basebody))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/21 09:29